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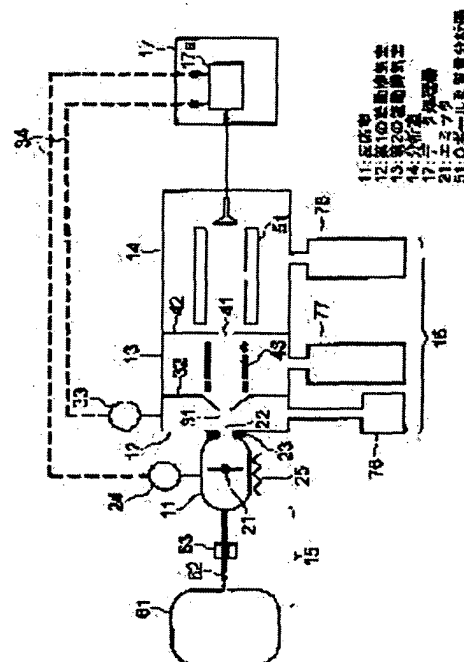
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## (54) METHOD AND DEVICE FOR ION ATTACHED MASS SPECTROMETRY

(57)Abstract:

**PROBLEM TO BE SOLVED:** To permit quantitative analysis in a method and a device for ion attached mass spectrometry.

**SOLUTION:** This device for ion attached mass spectrometry is provided with a reaction chamber 11 for attaching metal ion of positive charge to detected gas; a mass spectrometer 51 for separating and detecting the mass of the detected gas; an analysis chamber 14 where the mass spectrometer is installed; differential exhaust chambers 12, 13 connecting the reaction chamber to the analysis chamber; and a data processor 17 for inputting and computing mass signals from the mass spectrometer. A vacuum gages 24, 33 are further provided for measuring the total pressure of a pressure reduced atmosphere of the reaction chamber, differential exhaust chambers and analysis chamber in the pressure reduced atmosphere, and a measured total pressure signal from the vacuum gages during measurement is inputted to one of the data processor, a lead-in mechanism and an exhaust mechanism. The data processor includes an arithmetic means 17a for quantitatively analyzing each component making use of the fact that the sensitivity of each component has total pressure dependency of the pressure reduced atmosphere and that the total pressure dependency is different component by component.



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